

EFFECT OF NEGATIVE AND POSITIVE FIELD ON P-TYPE CuInTe FILMS HAVING EXCESS COPPER AND INDIUM

Masoud Dashtiani

Physics Department, Hormozgan University ,Bandar Abbas _69145 ,Iran

E-mail: masouddashtiani @ yahoo.com

Tell: ++98 761 7760012

Mobil: ++98 917 157 4964

Abstract

Significant effect of negative and positive field on transport properties of semiconductor ternary chalcopyrite are investigated. This paper will review a new type of relation which is presented for Silver- Mica- CuInTe_2 films, MIS structure. , interface due to application of gate field. Studies of the variation of Hall Co-efficient and Hall Mobility with temperature at various gate field for well defined P- CuInTe_2 films MIS structure, also variation of effective field effect mobility with temperature, $\mu_{FE} \propto T^{\delta}, \delta' \sim 0.7$.

KEYWORDS: ternary, chalcopyrite, MIS structure, Hall Co-efficient, Hall Mobility, gate field

Introduction

CuInTe_2 is a copper ternary chalcopyrite compound semiconductor of family $A^I\text{-B}^{III}\text{-X}^{VI}_2$. They are direct band gap semiconductor which is in optimal range for terrestrial solar energy [1-4]. Various investigation have reported the physical, optical and electrical properties of CuInTe_2 [5-8]. Most of the work has been reported on either single crystal or bulk polycrystalline specimens. In order to interpret the surface properties thus influence results from the fact that the field produced by surface charge penetrates to a great depth in the semiconductor and thus effects the electrical transport phenomena. Transport properties of semiconductor ternary chalcopyrite crystal have drawn considerable interest due to their potential application in electronic devices [9-12].

MIS Structure

Field effect has proved to be a powerful tool in studying surface phenomena, this electric field can be produced in a number of ways. A simple way to active this is to fabricate a metal- Insulator/ Oxide- semiconductor (MIS/MOS) structure and to apply a capacitive field. The MIS structure was first employed in the study of surface properties of thermally oxidized silicon by Terman [13], Lehovac and Slodskoy [14].

The MIS/MOS structures have potential applications in electronic and for studying fundamental from narrow band-gap semiconductors are becoming important in monolattic infrared imaging application, MIS structure has received much attention due to its application in solar cell, the existence of the thin insulator ($<40 \text{ \AA}$) improves the open – circuit photovoltage and the dark current [15-17].

Experimental

This films of CuInTe_2 $1\mu\text{m}$ thicknesses were thermally evaporated from the above charge in stoichiometric as well as In excess 2at% and Cu excess 2at% , [18,19]. The variation of Hall co-efficient with temperature ($\log R_H$ vs $1/T$) at various gate field for well defined p- CuInTe_2 films in MIS structures given in **Figures 1,2,3**.

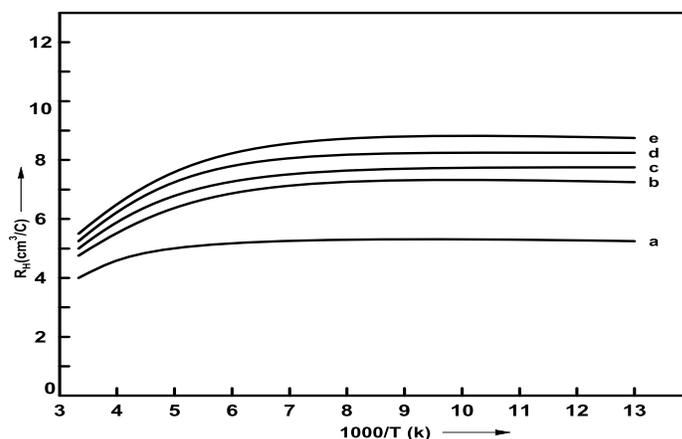


Figure 1: Variation of $\log R_H$ vs $1/T$ for p- CuInTe_2 thin films at various gate field

a) $-2 \times 10^5 \text{ V Cm}^{-1}$ b) $-1 \times 10^5 \text{ V Cm}^{-1}$ c) Zero d) $+1 \times 10^5 \text{ V Cm}^{-1}$ e) $+2 \times 10^5 \text{ V Cm}^{-1}$

of R_H remains constant in the low temperature 77- 180 ° K and for In excess the value is 77- 200 ° K.

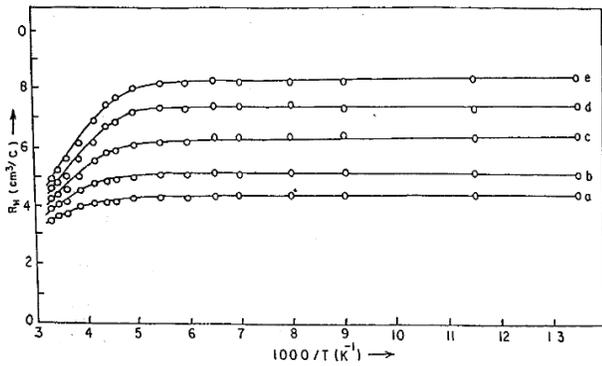


Figure 2: Variation of $\text{Log}R_H$ vs $1/T$ for p-CuInTe₂ thin films having 2at.% excess copper at various gate field a) $-2 \times 10^5 \text{ V Cm}^{-1}$ b) $-1 \times 10^5 \text{ V Cm}^{-1}$ c) Zero d) $+1 \times 10^5 \text{ V Cm}^{-1}$ e) $+2 \times 10^5 \text{ V Cm}^{-1}$

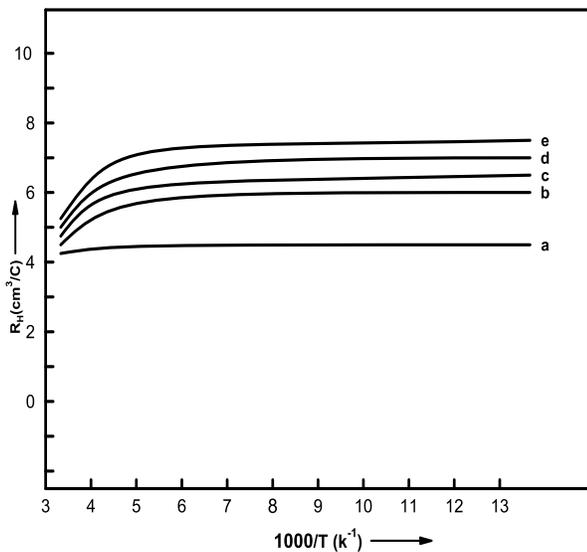


Figure 3: Variation of $\text{Log}R_H$ vs $1/T$ for p-CuInTe₂ thin films having 2at.% excess Indium at various gate field a) $-2 \times 10^5 \text{ V Cm}^{-1}$ b) $-1 \times 10^5 \text{ V Cm}^{-1}$ c) Zero d) $+1 \times 10^5 \text{ V Cm}^{-1}$ e) $+2 \times 10^5 \text{ V Cm}^{-1}$

It is find from these figures that in the absence of any gate field, the values of R_H for as grown films practically constant in low temperature range 77-170°K, showing the behavior of a typical degenerate semiconductor. R_H found to decrease with the rise of temperature at higher temperature 170 °K. The decrease of R_H can be attributed to the fact that contribution due to grain-boundary potential starts above 170° K. Where as for the films having Cu in excess the value

The variation of Hall mobility μ_H as a function of temperature ($\log \mu_H$ vs $1/T$) at various gate field for as-grown p-type CuInTe₂ thin film and also for the films having

2at% excess Indium Fig.4. and thin films with 2at% excess Copper Fig. 5. It has been observed that the value of μ_H for p-type CuInTe₂ thin films temperature decrease with negative gate field, while the effect of a positive gate field is to increase the μ_H This type of variation of the μ_H with various gate fields can be due to the fact that the gate field causes a change in the free carrier consideration. μ_H increases with increase of temperature at any gate field, which can be attributed to the concentration of the grain boundary scattering mechanism.

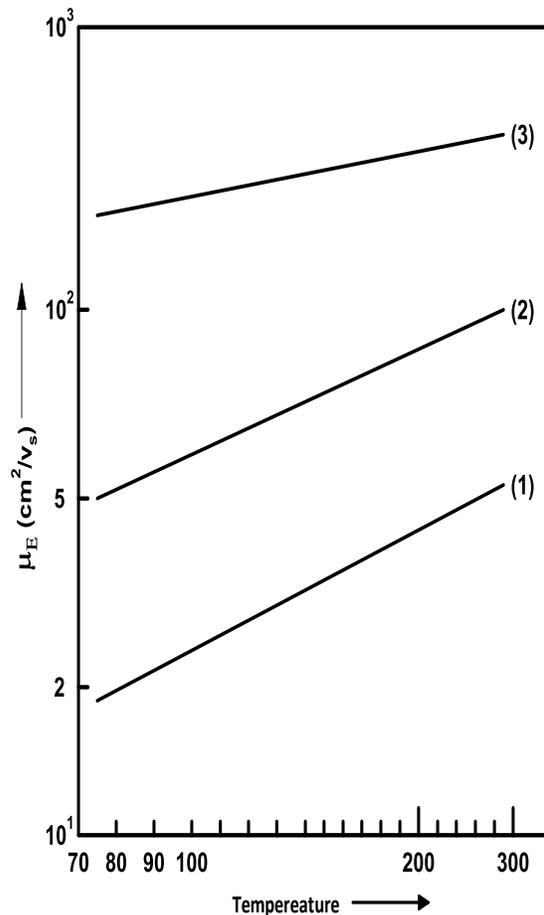


Figure 4: Variation of field effect mobility μ_{FE} with temperature ($\text{Log} \mu_{FE}$ vs $\text{Log} T$) for 1) as-grown 2)2at.% excess Copper 3)2at.% excess Indium

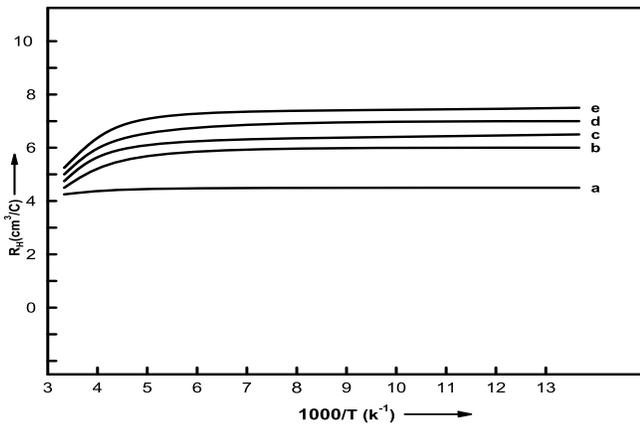


Figure 5: Variation of Log μ_H vs $1/T$ for p-CuInTe₂ thin films having 2at.% excess copper at various gate field a) -2×10^5 V Cm⁻¹ b) -1×10^5 V Cm⁻¹ c) Zero d) $+1 \times 10^5$ V Cm⁻¹ e) $+2 \times 10^5$ V Cm⁻¹

The values of grain boundary potential $e \phi_B$ have been obtained at various gate field, are shown in Table 1. it may be seen from this table that the value of $e \phi_B$ increases with the increase of negative gate fields, whereas the effect of a positive gate field is opposite. The increase in $e \phi_B$ suggests that the contribution of grain boundary scattering increases with the increase of negative gate field.

Table1: The Value of grain boundary potential for various gate field

S.No.	Applied gate field $\times 10^5$ V / Cm ²	$e \phi_B$ (meV) for p-CuInTe ₂		
		As grown	2at . % Excess Cu	2at . % Excess In
1.	-2.0	68.7	42.1	34.4
2.	-1.0	63.1	40.8	32.9
3.	Zero	50.9	39.0	30.0
4.	+1.0	47.2	37.7	28.2
5.	+2.0	45.6	35.8	25.2

The σ vs V_g conductivity data for various gate field at different temperature has been analysed to calculate the effective field effect mobility μ_{FE} as a function of temperature [20]. By considering the value of the total charge induced at the interface as a function of applied gate field. It may be observed from figures, that the slope of the curves, for any given temperature, vary with the applied field. The maximum slope of (σ - Q_s) curves were calculated the effective field effect mobility μ_{FE} with temperature ($\log \mu_{FE}$ vs $\log T$) is shown in Fig. 5. it can be observed that the value of μ_{FE} rises with the increase of temperature in accordance with the rela-

tion $\mu_{FE} \propto T^{\delta'}$. the value of δ' calculated from the temperature variation of μ_{FE} is found to be 0.7 indicates that charge fast interface traps and the surface states charge scattering are the dominating scattering mechanisms. It can be observed from related figure that the value of μ_{FE} is high for 2at. % Indium excess CuInTe₂ thin film. To study the effect of surface states with temperature, the value of excess

charge in the space-charge region, $e |\Delta p|$ was calculated. The value of $e |\Delta p|$ for these films at different temperatures are shown in Table 2.

Table2: The Value of Induced charge for defiance temperature

(The Total induced charge = 10.5×10^8 c Cm⁻²)

S.No.	Temperature (°K)	$e \Delta N \times 10^8$ c Cm ⁻² p-CuInTe ₂		
		As grown	2at . % Excess Cu	2at . % Excess In
1.	77	6.6	6.8	8.3
2.	100	7.0	6.8	8.8
3.	120	6.5	7.2	9.1
4.	170	7.1	6.9	8.5
5.	232	6.0	7.3	7.6
6.	295	6.0	7.0	8.3

It can be seen from this table that the values of ($e |\Delta p|$) are nearly constant with temperature and a very little contribution of change in occupation by the surface state and traps with temperature, to the temperature dependence of μ_{FE} .

Conclusion

As grown thin films of CuInTe₂ evaporated in vacuum are found to be p-type polycrystalline with large number of 112-oriented grains. It is also seen that the crystalline nature of the films improved with, increase In- contents. Resulting in p-type conductivity, that the composition of as grown charge to be, Cu_{0.9}In_{1.0}Te_{2.1} which is near to the desired stoichiometric and it have a very small excess Te. The electrical, measurement σ , R_H in these In-excess films show that monotonically, increase, throughout the temperature range 300 to 77 °k. the study of temperature variation of conductivity show that the dominant conduction in the films up to 2at.% excess In-content is variable range hopping at temperature 200-77 °k while grain boundary activation is more predominant at higher temperature the value of activation energy E_a , for as-grown film, is 58.4 meV and for 2at% excess Indium



content is 50.99 meV where it decreases by increase of excess of In-concentration and the value of grain boundary barrier potential $e\phi_B$ is more for as-grown thin films. The value of ϕ_B is found to decrease with the increase of excess In-content suggesting the possibility of shortening of grain boundaries with the addition of excess Indium concentration. Know the study of the field effect on MIS structure of p-type CuInTe_2 thin films revealed that the effect of positive gate field was to deplete the majority charge carriers, while the effect of negative gate field was to accumulate the charge carriers. The study of effective field effect mobility on p- CuInTe_2 as-grown, and addition of In, Cu in excesses e.g. 2at%, MIS structure revealed that the surface state charge scattering mechanisms dominate the scattering processes. Finally, it has been seen there is not any change in the occupancy of the surface states in these films.

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- ## Biographies
- MASOUD DASHTIANI** received the B.S. degree in Electronic from the University of korokshtra, Ambala Cantt, India, in 1984, the M.S. degree in Physics (Electronic) from the University of Meerut, Mozafar Nagar City, Meerut State,India in 1987, and the Ph.D. degree in Electrical Optical properties of Semiconductors from the University of Delhi , Delhi City, India 1991, and post Ph.D. in photoconductivity Semiconductors University of Delhi , Delhi City, India 1993, respectively. Currently, He is an associate Professor of Physics , at University of Hormozgan Bandar Abbass , Hormozgan State,Iran. His teaching and research areas photoconductivity Semiconductors, Electrical Optical properties of Semiconductors .
masouddashtiani @ yahoo.com